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**(54) Title (EN):** HYGIENE MONITORING SYSTEM

**(54) Title (FR):** SYSTEME DE SURVEILLANCE/CONTROLE DE L'HYGIENE

**(57) Abstract:**

**(EN):** A hygiene monitoring system (100), which incorporate various features of the present invention, monitor location of persons (110) in a facility, location of equipment (115) in the facility, activities performed by persons (110) in the facility, activities performed by equipment (115) in the facility, and/or activities performed on equipment (115) in the facility. From such gathered information, the hygiene monitoring system (100) determines whether certain actions (e.g. washing of a person's hands (107), washing of a piece of equipment (115) need to take place in order to comply with a hygiene policy defined for the facility. The hygiene monitoring system (100) may evaluate level of compliance with the hygiene policy, and provide persons (110) with information (e.g. alerts, reminders, etc.) which aid in increasing the level of compliance with the hygiene policy.

**(FR):** Un système (100) de surveillance/contrôle de l'hygiène comprenant plusieurs caractéristiques de la présente invention, surveille la position de personnes (110) dans une unité, la position du matériel (115) dans l'unité, les activités menées par les personnes (110) dans l'unité, les activités effectuées par le matériel (115) de l'unité et/ou les activités accomplies sur le matériel (115) de l'unité. A partir de ces informations collectées, le système (100) de surveillance/contrôle détermine si certaines actions (par exemple, le lavage des mains (107) d'une personne, le nettoyage d'une partie de matériel (115)) doivent être effectuées pour se conformer aux règles d'hygiène définies pour l'unité. Le système (100) de surveillance /contrôle de l'hygiène peut évaluer le niveau de conformité aux règles d'hygiène et fournir aux personnes (110) des informations (par exemple des dispositifs d'avertissement, des aide-mémoire, et autres) qui aident à accroître le niveau de conformité aux règles d'hygiène.

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